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Patents

- » 6,069,739, Method and lens arrangement to improve imaging performance of microlithography exposure tool, 5/30/2000
- » 6,021,009, Method and apparatus to improve across field dimensional control in a microlithography tool, 2/1/2000
- » 5,946,079, Photolithography method using coherence distance control, 8/31/1999
- » 5,840,448, Phase shifting mask having a phase shift that minimizes critical dimension sensitivity to manufacturing and process variance, 11/24/1998
- » 5,801,821, Photolithography method using coherence distance control, 9/1/1998
- » 5,532,090, Method and apparatus for enhanced contact and via lithography, 7/2/1996
- » 5,498,579, Method of producing semiconductor device layer layout, 3/12/1996
- » 5,424,154, Lithographic enhancement method and apparatus for randomly spaced structures, 6/13/1995
- » 4,767,215, Lens characterization apparatus and method, 8/30/1988
- » 4,672,420, Integrated circuit structure having conductive, protective layer for multilayer metallization to permit reworking, 6/9/1987
- » 4,580,332, Forming a conductive, protective layer for multilayer metallization, 4/8/1986
- » 4,529,685, Method for making integrated circuit devices using a layer of indium arsenide as an antireflective coating, 7/16/1985